

AMENDMENTS TO THE SPECIFICATION:

Please replace paragraph 3 on page 11, with the following amended paragraph:

Fourth Embodiment

The effects described with reference to the first and second embodiments can be attained by dipping a photomask substrate in H₂ gas dissolved water mixed with a small amount of aqueous ammonia introduced into a conventional overflow tank 301, as shown in Fig. 2. The washing effect is further improved by applying ultrasonic waves via an ultrasonic oscillator 302.